Utilization of New Concepts in Supporting the Demand for Sustainable Materials by Developing Next Generation Materials, as well as Exploring New Reaction Routes that Benefit from the Growing Use of Continuous Flow Monitoring and Control Technology

Overview and Workshop Theme: A key enabler of the move to a Circular Economy will be process intensification which offers sustainable processing of lower volume distributed waste streams to generate a broad range of new platform chemicals including a growing list of biomass mass derived molecules. Using new catalyst in one pot and cascade chemistries, these new starting materials including nanomaterials are being converted to a range of new composites and materials with advanced properties. The 2020 Rome meeting will build on this theme of sustainable production and will focus on next generation materials. In addition, there will be an emphasis on exploring new reaction routes that benefit from the growing use of continuous flow technology and effective monitoring and control concepts. The evolution of flow microscale reaction technology has led to a wide range of process intensification developments in the various steps that result in the ability to rapidly evaluate and optimize new reaction routes as well as offering more cost-effective processing. The key next step is the integration of these unit operations into end-to-end optimized continuous processes.

CPAC has an established track record in fostering academic and industrial interactions. For more information please see Rome Workshop 2020 (http://mkcontrol.com/rome-meeting-2020.html). The registration fee is $750 USD. Contact Mel Koch (kochm@uw.edu) or Nan Holmes (nsh@uw.edu) for additional information.

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